

FORM PTO-1449 (MODIFIED)

ATTORNEY DOCKET NO.

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LIST OF PATENTS AND
PUBLICATIONS

SP01-331

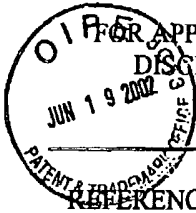
10/086,231

FOR APPLICANTS INFORMATION
DISCLOSURE STATEMENT

APPLICANT Bowden et al.

FILING DATE February 27, 2002

GROUP:



REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
PL	AA	2,326,058	8/3/43	Nordberg	100	52	
AL	AB	4,501,602	2/26/85	Miller et al.	65	18.2	
CL	AC	5,043,002	8/27/91	Dobbins et al.	65	3.12	
EL	AD	5,152,819	10/6/92	Blackwell et al.	65	3.2	
EL	AE	5,154,744	10/13/92	Blackwell et al.	65	3.2	
EL	AF	5,686,728	11/11/97	Shafer	250	492.2	
EL	AG	5,970,751	10/26/99	Maxon et al.	65	414	
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		Document Number	Date	Country	Class	Sub-Class	Translation Yes	No
AL	AJ	WO 01/07967	2/1/01	PCT	G03C	5/00	X	
EL	AK	WO 01/08163	2/1/01	PCT	G21K	5/00	X	
CL	AL	WO 01/75522	10/11/01	PCT	G03F	1/14	X	
EL	AM	WO 00/48775	8/24/00	PCT	B23B		X	
EL	AN	WO 02/32622	4/25/02	PCT	B24B	7/24	X	
EL	AO	WO 02/26647	4/4/02	PCT	C03B	37/016	X	
EL	AP	WO 02/32616	4/25/02	PCT	B23P	13/04		
EL	AQ	EP 0 903 605A2	3/24/99	EPO	G02B	13/14	X	
EL	AR	EP 1 106 582A2	6/13/01	EPO	C03B	19/10	X	

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1/27/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609: draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

PL	A1	P. Shultz & H. Smith, Ultra-Low-Expansion Glasses and Their Structure in the SiO ₂ -TiO ₂ System, Amorphous Materials, papers presented to the Third International Conference on the Physics of Non-Crystalline Solids, held at Sheffield University, September 1970
CL	A2	George H. Beall, Industrial Applications of Silica, Reviews in Mineralogy, Vol. 29 (Silica), (1994), 469-505.
CL	A3	Charles Gwyn et al., Extreme Ultraviolet Lithography, November 1999, 97-141.
CL	A4	EUV Lithography NGL Technology Review, June 9, 1999, Chicago, Illinois
CL	A5	Charles Gwyn et al., Extreme Ultraviolet Lithography, 1-6. (NO DATE AVAILABLE)
CL	A6	William M. Tong et al., Substrates Requirements For Extreme Ultraviolet Lithography, Information Science & Technology, Lawrence Livermore National Laboratory, December 1999.
CL	A7	O.V. Mazurin et al., Crystallization of Silica and Titanium Oxide-Silica Corning Glasses (Codes 7940 & 7971), Journal of Non-Crystalline Solids 18, (1975) 1-9.
CL	A8	ISIMOTO CO. LTD., Purity and Chemical Reactivity, http://www.isimoto.com/isimoto/english/feature1.html , 1-3, 5/17/99
CL	A9	ISIMOTO CO. LTD., Product Information, http://www.isimoto.com/isimoto/english/product_info.html , 1-4, 5/17/99
CL	A10	Rapid Prototyping, http://mtiac.itri.org/pubs/rp/rp1.htm 11/5/01
PL	A11	Products: SLS (R) Systems - Introduction, Vanguard™ and Vanguard™ HS, http://www.3dsystems.com/products/slssystems/vanguard/index.asp?promo= 11/5/01
CL	A12	Corning, Semiconductor Materials ULE Zero Expansion Glass, http://www.corning.com/semiconductormaterials/products_services/ule.asp 10/31/01
CL	A13	Richard H. Stulen et al., Extreme Ultraviolet Lithography, IEEE Journal of Quantum Electronics, Vol. 35, No. 5, May 1999, 694-699..

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